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## THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Choi et al. PATENT APPLICATION  
Serial No.: 09/698,317 Group Art Unit: 2859  
Filing Date: October 27, 2000 Examiner: Unassigned  
For: HIGH-PRECISION ORIENTATION ALIGNMENT AND GAP CONTROL STAGES  
FOR IMPRINT LITHOGRAPHY PROCESSES

INFORMATION DISCLOSURE STATEMENT

Commissioner  
for Patents  
Washington, D.C. 20231

Sir:

The following information is submitted in compliance with Applicants' duty of disclosure under 37 C.F.R. § 1.56. Form PTO-1449 and a copy of each reference recited below accompanies this document. It is respectfully requested that the cited information be expressly considered during the prosecution of this application, and the references be made of record therein and appear among the "references cited" on any patent to issue therefrom.

ISSUED PATENTS

| Patent Number | Inventor        | Grant Date    |
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FOREIGN PATENT DOCUMENTS

| <u>Document Number</u> | <u>Inventor</u> | <u>Pub. Date</u> |
|------------------------|-----------------|------------------|
| WO 92/17883            | Olsson          | Oct. 15, 1992    |
| WO 98/10121            | Olsson et al.   | Mar. 12, 1998    |
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Lin, "Multi-Layer Resist Systems", Introduction of Microlithography", American Chemical Society, 1983, pp. 287-350, IBM T.J. Watson Research Center, Yorktown Heights, NY 10598.

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Chou et al., "Imprint of Sub-25nm Vias and Trenches in Polymers", Applied Physics Letters, Nov. 20, 1995, pp. 3114-3116, vol. 67(21).

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Respectfully Submitted,



Kenneth C. Brooks  
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Application Number 09/698,317

October 27, 2000

First Named Inventor Choi et al

Group Art Unit 2859

Examiner Name \_\_\_\_\_

Attorney Docket Number: BA09-06102

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## FOREIGN PATENT DOCUMENTS

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|------------------------|------------------|
| Application Number     | 09/698,317       |
| Filing Date            | October 27, 2000 |
| First Named Inventor   | Choi et al.      |
| Group Art Unit         | 2859             |
| Examiner Name          | Unassigned       |
| Attorney Docket Number | PA09-06V02       |

#### OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

Examiner  
Signature

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